# SEP 2 2 2003 8

## RESPONSE UNDER 37 C.F.R. 1.116-EXPEDITED PROCEDURE EXAMINING GROUP 2829

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.

10/099,641

Applicants:

Wilbur G. Catabay and Richard Schinella

Filed:

March 15, 2002

Title

LOW K DIELECTRIC COMPOSITE LAYER FOR INTEGRATED

CIRCUIT STRUCTURE WHICH PROVIDES VOID-FREE LOW K DIELECTRIC MATERIAL BETWEEN METAL LINES WHILE

MITIGATING VIA POISONING

Grp./ A.U.

2829

Examiner

Lisa A. Kilday

Docket No.

99-102/1D

### **CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

September 16, 2003

(Date of Deposit)

John P. Taylor, Reg. No. 22,369

Signature •

September 16, 2003

Date of Signature

### RESPONSE TO FINAL REJECTION

Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Date: September 16, 2003

In response to the Final Rejection mailed July 16, 2003, please amend the application as follows: